Photomask Japan 2018 Program at a Glance

April 18 (Wed.)

Symposium Program

as of April 16, 2018

10:00 - 10:10 Opening

10:10 - 10:40 Keynote
Invited Talk: Evolutional Memory Technology
Presenter: Nahomi Aoto (Micron Memory Japan)

10:40 - 12:10
Session 1: NIL
Invited Talk (EMLC best) 10:40 - 11:10
Characterization and application of vertical material contrast generated by VUV exposure: making smooth 3D polymer micro-optics
Presenter: Robert Kirchner (Technical University of Dresden)

12:10 - 13:20 Lunch

13:20 - 14:40
Session 2: FPD Photomasks

14:40 - 15:00 Break

15:00 - 15:50
Session 3: Writing & Metrology
Invited Talk 15:00 - 15:30
Update on Multi-Beam Writing
Presenter: Mathias Tomandl (IMS)

15:50 - 16:30
Session 4: Process & Repair

16:30 - 16:50 Break

16:50 - 18:00
Session 5: EDA & Lithography
Invited Talk 16:50 - 17:20
Novel 3-Dimensonal Photo Lithography Using Built-In Lens Mask
Presenter: Yoshihiko Hirai (Osaka Prefecture University)

April 19 (Thu.)

9:00 - 10:30
Session 6: EUV Masks (I)
Invited Talk 9:00 - 9:30
eBeam Initiative Surveys Report Greatly Increased Confidence in EUV and Mask Process Correction Requirements
Presenter: Aki Fujimura (eBeam Initiative)

10:30 - 10:50 Break

10:50 - 11:50 Session 7:
EUV Source for Inspection

11:50 - 13:20 Lunch

13:20 - 15:00 Session 8:
25th Anniversary Special Session

15:00 - 15:20 Break

15:20 - 17:00
Session 9: Poster Session

9A: Mask Technologies
9B: Mask/Lithography Related Technologies in Academia

17:00 - 20:00 Banquet

April 20 (Fri.)

9:00-10:40
Session 10: EUV Masks (II)
Invited Talk (BACUS best) 9:00 - 9:30
Presenter: (TBD)

Invited Talk 9:30 - 10:00
Progress on Actinic Blank Inspection tool and application to EUV mask observation
Presenter: Hiroki Miyai (Lasertec)

10:40-11:00 Break

11:00-12:10
Session 11: EUV Masks (III)
Invited Talk 11:00 - 11:30
AIMSTM EUV Platform: Going Beyond Actinic Review of EUV Photomasks
Presenter: Martin Dietzel (Carl Zeiss)

12:10-13:40 Lunch

13:40-15:20
Session 12: EUV Masks (IV)
Invited Talk: BACUS Panel 13:40 - 14:10
"HVM EUV Lithography: Managing without Actinic Patterned Mask Inspection"
Presenter: Jed H. Rankin (GlobalFoundries Inc.)
Invited Talk 14:10 - 14 :40
NXE pellicle Industry Update
Presenter: Derk Brouns (ASML)

15:20-15:30 Closing

Session 8

"Mask Technology", the key of Moore's Law Scaling
Presenter: Shinji Okazaki (ALITECS Corporation)

History of VSB Mask Writer and Future of Multi-beam Mask Writer
Presenter: Noriaki Nakayamada (NFT)

Greeting Message for PMJ 25th Anniversary from EMLC
Presenter: Uwe Behringer (EMLC)

Greetings Message for PMJ 25th Anniversary from BACUS
Presenter: Jim Wiley (ASML)